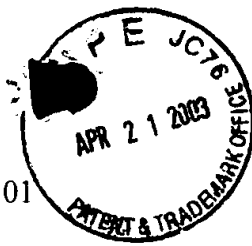


Docket No.: 50090-301



PATENT

#4
4/22/03

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Toshihiro YAMASHITA, et al.

Serial No.: 09/901,038

Group Art Unit: 1765

Filed: July 10, 2001

Examiner: D.V.D. Nguyen

For: PLASMA PROCESSING SYSTEM IN WHICH WAFER IS RETAINED BY
ELECTROSTATIC CHUCK, PLASMA PROCESSING METHOD AND METHOD OF
MANUFACTURING SEMICONDUCTOR DEVICE

REC'D
APR 22 2003
GROUP 1700

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
Washington, DC 20231

Sir:

Noting the Office Action of March 25, 2003 wherein restriction has been required, Applicant(s) hereby elect Group I (claims 1-8) for prosecution in the above-identified application.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT, WILL & EMERY

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Date: April 21, 2003